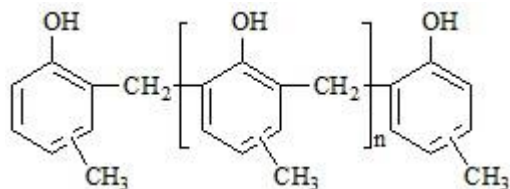


# Phenolic resin for Photoresist

English Name: Cresol-formaldehyde Novolac for Photoresist

## Molecular Structure:

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## Product Introduction:

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The product is a thermoplasticity condensation polymer prepared with cresol and formaldehyde under the circumstance of catalyst. In the process, the resin's molecular weight and distribution, the ratio of cresol isomer and the connection manner of methylene group are strictly controlled with our technique and intergradient.

## Specification:

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Property	Specification
Apperance	Light yellow slice
Molecular Weight (GPC)	Mn: 1000~1100; Mw: 5000~6000
Softening Point (°C)	140~160
Free monomer content (% , <)	0.5

## Application:

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The phenolic resin is one of the key components of g-line and i-line photoresist. Due to its great thermostability and anti-corrosion property, it can be used to prepare resin picture with high resolution.

## Package and Storage:

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25kg per bag, 25kg per can. Product should avoid directly sunshine and should be kept in the clean and ventilative room in the case of room temperature. It can be kept for 6 months.